

**IN THE CLAIMS:**

**Kindly enter the following amended claims:**

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1. (Previously Amended) A belt comprising (a) a polishing surface for polishing a workpiece in a linear chemical mechanical polishing system and (b) a side opposite the polishing surface, the belt forming an endless loop, an improvement comprising at least one aperture from the polishing surface through the side opposite the polishing surface so that the aperture is substantially free of a window, the aperture positioned on the belt to allow monitoring of the workpiece through the aperture;

one of a notch along a first edge of the belt and trigger hole, the notch or trigger hole positioned relative to the aperture;

a monitor positioned to sense the workpiece through the aperture;  
and

a sensor positioned such that passing of the trigger hole or notch activates the monitor.

2. (Original) The belt of Claim 1 wherein the belt has two substantially parallel edges and the aperture is centered between the two substantially parallel edges.

3. (Original) The belt of Claim 1 wherein the aperture comprises a substantially circular shape.

4. (Original) The belt of Claim 1 wherein the belt has at least three apertures through the belt.

5. (Original) The belt of Claim 4 wherein the at least three apertures are spaced evenly around the endless loop.

- 3 -

6. (Previously Amended) The belt of Claim 1 wherein the one of the trigger hole and the notch comprises a notch along a first edge of the belt, the notch positioned relative to the aperture.

7. (Previously Amended) The belt of Claim 1 wherein the one of the trigger hole and notch comprises a trigger hole positioned relative to the aperture.

8. (Original) A system for polishing a workpiece in a chemical mechanical polishing process, the system comprising:  
a monitor; and  
an endless belt positioned adjacent to the monitor, the endless belt having at least one aperture through the belt wherein a path through the aperture from the workpiece to the monitor is unobstructed, the aperture being substantially free of a window.

9. (Original) The system of Claim 8 wherein the endless belt has two substantially parallel edges and the aperture is centered between the two substantially parallel edges.

10. (Original) The system of Claim 8 wherein the endless belt has at least three apertures.

11. (Original) The system of Claim 8 wherein the endless belt has a notch or trigger aperture along a first edge of the belt, the notch or trigger aperture positioned relative to the aperture, wherein activation of the monitor is responsive to a position of the notch or trigger aperture relative to the workpiece.

12. (Original) The system of Claim 8 further comprising a slurry dispenser positioned adjacent to a polishing side of the endless belt.

- 4 -

13. (Original) The system of Claim 12 further comprising a platen adapted to apply water to the endless belt.

14. (Original) The system of Claim 13 wherein the water is operable to prevent drying of the slurry and to substantially clear a platen of slurry.

15. (Original) The system of Claim 13 wherein the platen is adapted to apply air to the endless belt.

16. (Original) A method for polishing a workpiece in a chemical mechanical polishing process, the method comprising the steps of:

(a) passing an endless belt along a workpiece, the endless belt having an aperture through the belt, the aperture being free of a window; and

(b) measuring a property of the workpiece through the aperture, a path through the aperture for measuring the workpiece being unobstructed by the aperture in the belt.

17. (Original) The method of Claim 16 wherein step (a) comprises passing a plurality of spaced apart apertures along the workpiece.

18. (Original) The method of Claim 16 wherein step (b) comprising directing a beam of light at the workpiece through the aperture.

19. (Original) The method of Claim 16 further comprising:

(c) triggering step (b) in response to a position of a trigger notch or aperture relative to the workpiece.

20. The method of Claim 16 further comprising:

(c) applying slurry to a polishing side of the endless belt, a portion of the polishing side being adjacent to the workpiece.

- 5 -

21. (Original) The method of Claim 20 further comprising:  
(d) applying pressure to the endless belt with water.
22. (Original) The method of Claim 21 further comprising:  
(e) preventing blockage by dry slurry in aperture on a platen with the water of step (d); and  
(f) clearing slurry from the aperture on the platen with the water of step (d).
23. (Original) The method of Claim 21 further comprising:  
(e) applying pressure to the endless belt with air.
24. (Previously Added) The belt of Claim 1 further comprising a fluid platen adjacent the belt, the fluid platen operable to provide liquid and gas pressure to the belt.
25. (Previously Added) The belt of Claim 24 wherein the fluid platen is operable to provide water pressure at a center of the fluid platen and gas pressure outward from the center.
26. (Previously Added) The belt of Claim 1 further comprising a fluid platen adjacent the belt, the fluid platen operable to provide humidified air pressure.
27. (Previously Added) The belt of Claim 1 further comprising a source of suction adjacent the at least one aperture.
28. (Previously Amended) A belt comprising (a) a polishing surface for polishing a workpiece in a chemical mechanical linear polishing system and (b) a side opposite the polishing surface, the belt forming an endless loop, an

- 6 -

improvement comprising at least one aperture from the polishing surface through the side opposite the polishing surface so that the aperture is substantially free of a window, the aperture positioned on the belt to allow monitoring of the workpiece through the aperture; and

a fluid platen adjacent the side opposite, said fluid platen comprising an aperture to allow a light beam to pass through the platen and onto the workpiece, the fluid platen operable to provide liquid and gas pressure to said platen aperture to clear a slurry from said aperture of said platen.

29. (Previously Added) The belt of Claim 28 wherein the belt has two substantially parallel edges and the aperture is centered between the two substantially parallel edges.

30. (Previously Added) The belt of Claim 28 wherein the aperture comprises a substantially circular shape

31. (Previously Added) The belt of Claim 28 wherein the belt has at least three apertures through the belt.

32. (Previously Added) The belt of Claim 31 wherein the at least three apertures are spaced evenly around the endless loop.

33. (Previously Added) The belt of Claim 28 further comprising a notch along a first edge of the belt, the notch positioned relative to the aperture.

34. (Previously Added) The belt of Claim 28 further comprising a trigger aperture positioned relative to the aperture.

- 7 -

35. (Previously Added) The belt of Claim 28 wherein the fluid platen is operable to provide water pressure at a center of the fluid platen and gas pressure outward from the center.

36. (Previously Added) The belt of Claim 28 wherein the fluid platen is operable to provide humidified air pressure.

37. (Previously Added) The belt of Claim 28 further comprising a source of suction adjacent the at least one aperture.

38. (Previously Amended) A belt comprising (a) a polishing surface for polishing a workpiece in a chemical mechanical linear polishing system and (b) a side opposite the polishing surface, the belt forming an endless loop, an improvement comprising at least one aperture from the polishing surface through the side opposite the polishing surface so that the aperture is substantially free of a window, the aperture positioned on the belt to allow monitoring of the workpiece through the aperture; and

101  
a fluid platen adjacent the side opposite, said fluid platen comprising an aperture to allow a light beam to pass through the platen and onto the workpiece, the fluid platen operable to provide humidified air pressure to said platen aperture to clear a slurry from said aperture of said platen.

39. (Amended) A belt according to Claim 28, ~~wherein comprising:~~  
directing said liquid and gas pressure ~~is also directed to said belt aperture to~~  
~~prevent and preventing~~ a slurry from draining through said belt aperture onto said platen.

40. (Amended) A belt according to Claim 38, ~~wherein comprising:~~  
directing said humidified air pressure ~~is also directed to said belt aperture to~~

- 8 -

~~prevent~~ and preventing a slurry from draining through said belt aperture onto said platen.

41. (Original) A belt comprising (a) a polishing surface for polishing a workpiece in a chemical mechanical linear polishing system and (b) a side opposite the polishing surface, the belt forming an endless loop, an improvement comprising at least one aperture from the polishing surface through the side opposite the polishing surface so that the aperture is substantially free of a window, the aperture positioned on the belt to allow monitoring of the workpiece through the aperture; and a fluid platen adjacent the side opposite, said fluid platen comprising an aperture to allow a light beam to pass from a monitor through the platen and onto the workpiece, said fluid platen operable to provide a suction to said platen aperture to clear a slurry from said aperture of said platen.

42. (New) A belt according to Claim 38, comprising: applying suction to said belt aperture and to remove slurry and prevent damage to said platen.

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